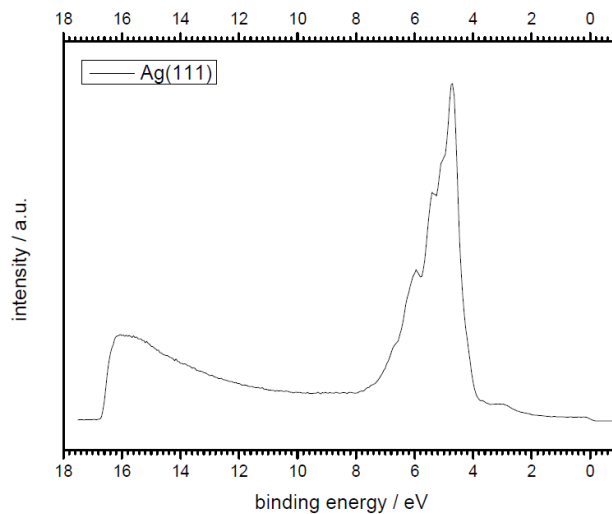


**Exercise 1: XPS**

- a) A  $MgK_{\alpha}$  X-ray source is used to record the XPS spectrum of palladium. At which kinetic energies would one expect peaks? Tipp: The most prominent peaks will originate from the 3s, 3p and 3d shells.
- b) Look at the two spectra of Teflon on the left. What might cause the difference, given that it is the same sample? How could one prevent it?

**Exercise 2: Ultraviolet photoelectron spectroscopy**

- a) UPS is very similar to XPS. What are the main differences?
- b) The following spectrum was measured on a clean Ag(111) surface using UV-light from a He-I source.



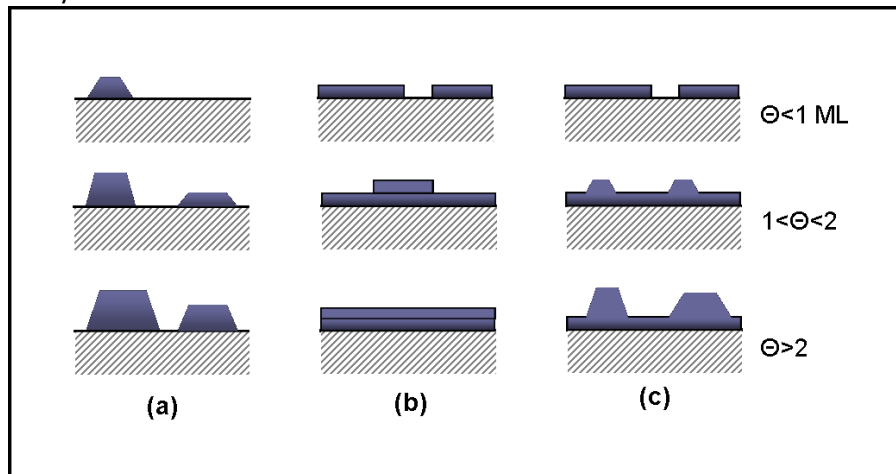
- i) Evaluate the work function of Ag(111).
- ii) What is the origin of the peaks at  $\sim 5$  eV?

**Exercise 3: Surface diffusion**

- a) The hopping rate of a nitrogen atom on the Fe(100) surface is  $10^{-3} \text{ s}^{-1}$  at 300 K and  $3 \times 10^{-2} \text{ s}^{-1}$  at 330 K. Estimate the diffusion coefficient and calculate the activation energy. Take into account that Fe is a bcc crystal with lattice parameter 2.87 Å. Assume the vibration frequency  $\nu_0$  is  $4.3 \times 10^{12} \text{ Hz}$ .
- b) Random-walk diffusion of Ag atoms occurs over the Si(111)  $\sqrt{3} \times \sqrt{3}$ -Ag surface. Estimate the mean displacement of the atom in a time of 1 s and 1 h at 450 °C.  $D_0 = 10^{-3} \text{ cm}^2 \text{ s}^{-1}$ ,  $E_{\text{diff}} = 0.33 \text{ eV}$ .

**Exercise 4: Thin film growth**

## a) Thermodynamics



- i) Name the three growth modes shown above.
- ii) Explain why a film grows on a substrate in each of the growth modes using the surface tensions.
- iii) How can you experimentally distinguish the three growth modes using XPS?
- iv) How can you distinguish them with RHEED?

- b) Kinetics: For the case of homoepitaxy, considering the parameters “substrate temperature” and “deposition rate”: how should one choose those parameters in order to obtain 2D or 3D growth? Explain.